

#28  
1/22/01

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of:

Sylvia H. Pas	Examiner: TBD
Serial No: TBD	Art Unit: TBD
Filed: 01/11/01	Docket No.: TI-22398
For: SYSTEM AND METHOD FOR INTEGRATED OXIDE REMOVAL AND PROCESSING OF A SEMICONDUCTOR WAFER	

PRELIMINARY AMENDMENT

January 11, 2001

Assistant Commissioner for Patents

Washington, DC 20231

Dear Sir:

Please amend the above referenced application as follows:

In the Specification:

Page 1, before line 1, insert --☒ This application claims priority under 35 USC §

119(e)(1) of provisional application numbers **60/178,647** filed **01/28/00**.--